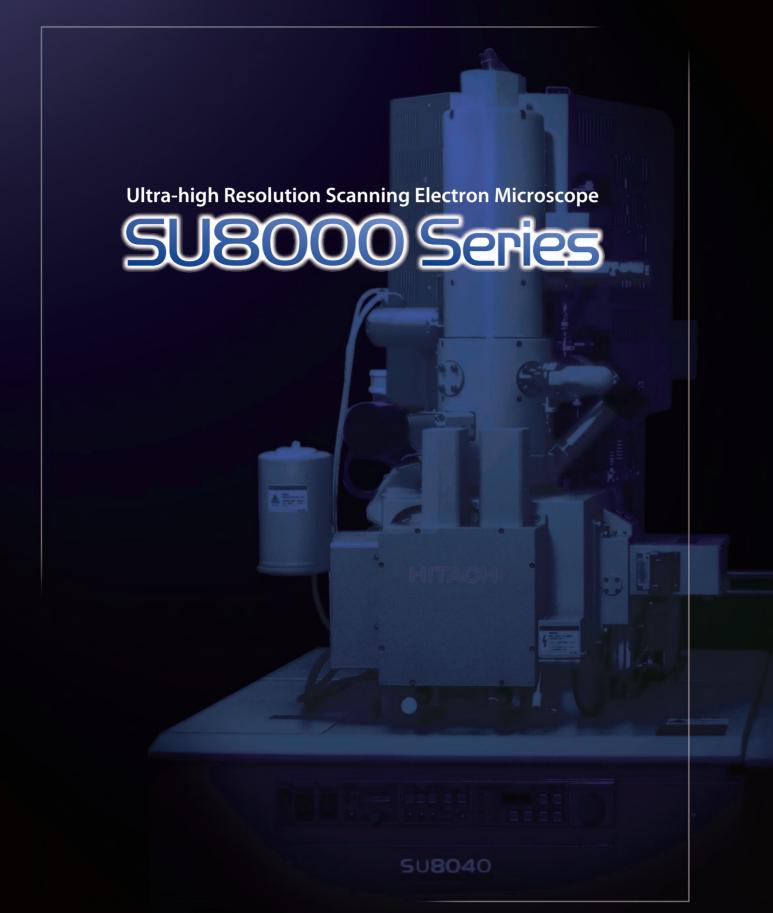
Hitachi HighTech



HITACHI

Powerful lineup for ultra high resolution microscopy

Nanotechnology fields, such as semiconductors, electronics, catalysis and other functional materials, biotechnology and pharmaceuticals are being researched world-wide as core competencies for next generation cutting-edge technologies. Ultra High Resolution FE-SEM has grown to be an indispensable tool to observe the fine surface structure of materials in a wide range of nanotechnology fields.

Hitachi High-Tech has developed the SU8000 Series to fulfill tomorrow's market needs. The new SU8000 Series has excellent imaging performance throughout the range, and offers a variety of stages, chambers and signal detection systems to meet the wide variety of customer-specific needs for ultra high resolution microscopy.



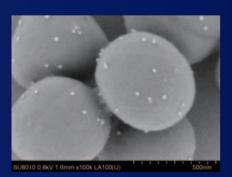
Sample : Al electrolytic capacitor Courtesy of St. Jude Medical, CRMD-U.S.A.

Features of the SU8000 Series

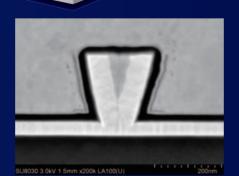
Ultra-high resolution imaging, even at ultra low accelerating voltage (SE resolution 1.3 nm at landing voltage 1.0 kV)
 A wide range of signal detection systems

- Lineup of four microscopes to meet the wide variety of applications for ultra high resolution microscopy
- User-friendly GUI, console and wide -format monitor for comfortable operation
- Wide range of optional accessories to meet customer-specific needs

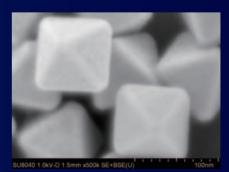




Sample : Staphylococcus aureus (immuno SEM) Courtesy of Medical Mycology Research Center, Chiba University Dr. Masashi Yamaguchi



Sample : Hard disc (magnetic head)

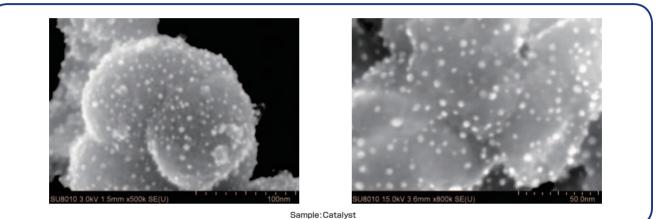


Sample : Single crystal line octahedral gold nanoparticle Courtesy of Department of Chemistry, Graduate School of Pure and Applied Sciences, University of Tsukuba Dr. Toshiharu Teranishi

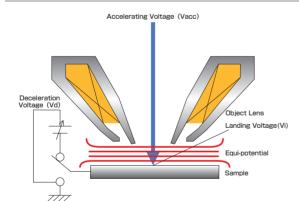
SU8010, entry level model for ultra high resolution microscopy

SU8010 has excellent performance as the entry level model in the SU8000 series. The combination of Semi-in-lens type objective lens and cold FE-gun with small energy spread delivers ultra high resolution imaging performance and flexible SE-BSE signal mixing using Hitachi's detector technology for absolute surface information, Z-number contrast and charge suppression.

Ultra high resolution imaging (Resolution 1.0nm/15kV)





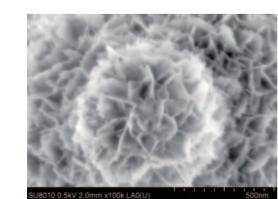


Beam deceleration function as standard (Resolution 1.3nm/1kV)

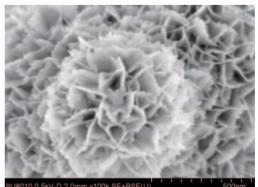
Beam deceleration applies a negative voltage (Beam deceleration voltage : Vd) to the specimen to decelerate the primary electron just before the beam interacts with the specimen. By using beam deceleration, landing voltage can be reduced as low as 100V with low lens aberration. As a result, ultra high resolution imaging of sample surface characteristics can be obtained at ultra low landing voltage.

Effect of beam deceleration

- High resolution imaging at low landing voltages
- Absolute surface information from the sample
- Less sample damage as a result of the low landing voltages available



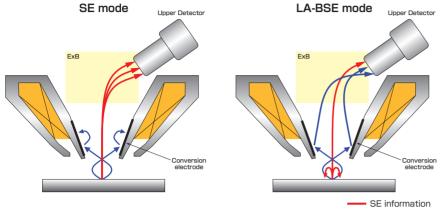
Beam deceleration function off



Beam deceleration function on

Sample : Al electrolytic capacitor Courtesy of St. Jude Medical, CRMD-U.S.A.

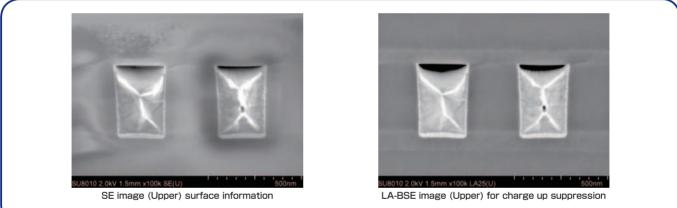
SE-BSE signal mixing function (Super ExB)



BSE information

Hitachi High-Tech's unique SE-BSE signal mixing function expands the signal detection capability. By changing the voltage of the signal conversion electrode in the objective lens, the SE-BSE signal ratio can be adjusted to any ratio (100 steps).

In non-conductive samples, low energy secondary electrons commonly show charge up contrast, which does not express, and may hide the correct sample information. By applying the signal mixing function, the secondary electron signal can be selectively or progressively suppressed, to optimize the true image contrast.







etector	SE resolution	1.Onm(Vacc 15kV,WD=4mm) 1.3nm(landing voltage1kV,WD=1.5mm)
lete	Top detector	_
	Upper detector	0
<u>ω</u>	Lower detector	0

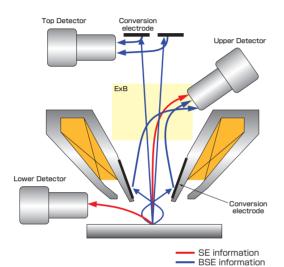
	Stage control		3-axis motor drive stage *5-axis motor drive stage(option)
Stage	Stage traverse range	Х	0~50mm
Sta		Υ	0~50mm
Specime		R	360°
		Т	-5 ~ 70°
g	۵ ۵		1.5 ~ 30mm
	Max. sample size		100mm dia. * 150mm dia. (Option)

SU8020

SU8020, additional flexibility of signal detection with its stunning triple detector system

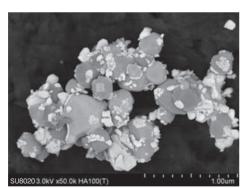
With the unique Top detector, additional signal collection is possible. Selective High angle backscattered electrons (HA-BSE) can be detected. The SU8020 offers pure Z-number compositional information using the Top detector, and voltage contrast from the absolute sample surface that has never been possible routinely before. Top, Upper and Lower triple detectors offer optimum signal collection. for many imaging applications.

Variety of signal detecting system for visualizing absolute surface information

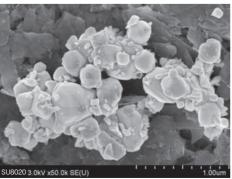


Triple detector system offers a variety of signal collection. Top detector can detect High angle BSE (HA-BSE), which has pure Z-number contrast with less topographical information. The Upper detector collects either the SE signal for surface topography/ voltage contrast, or user-selectable low angle BSE(LA-BSE), for both topographical information and compositional contrast. Both signals can also be mixed. The Lower detector is used for longer working distance SE imaging of surface topography.

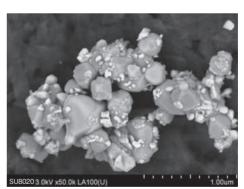
Signal name	Detector	Signal information		
HA-BSE	Тор	Compositional/Crystal information		
LA-BSE	Upper	Compositional/Topographic information		
SE Upper Surface information (Includi		Surface information (Including voltage contrast)		
Lower Lower		Topographic contrast		



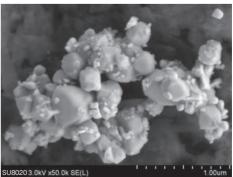
HA-BSE image(Top) : compositional information



SE image (Upper) : surface information



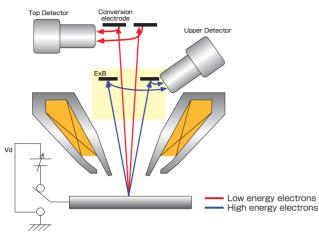
LA-BSE image(Upper) : Topographic+compositional information



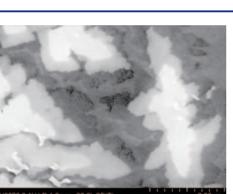
Lower image (Lower) : Topographic information

Sample : Photocatalyst Courtesy of Nagaoka University of Technology, Faculty of Engineering, Dr. Kazunori Sato

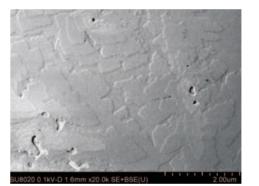
Signal detection with Beam deceleration



In the beam deceleration mode, it is possible to discriminate between low energy SE's and high energy BSE electrons by selecting either the Top detector or Upper detector in the GUI. Low energy secondary electrons now detected by the Top detector show voltage contrast in deceleration mode. Alternatively, high energy electrons detected by the Upper detector are far less susceptible to charge-up effect. Even if the sample is less conductive, it is possible to observe the sample without chargeup contrast. In addition, fine topographical information can still be obtained as the Upper detector now collects electrons generated at low angle.



SE image(Top) : Surface voltage contrast



SE + BSE image(Upper) : Topographic information

Sample : Pentacene



etector	SE resolution	1.0nm(Vacc 15kV,WD=4mm) 1.3nm(landing voltage1kV,WD=1.5mm)
ete	Top detector	0
	Upper detector	0
SE	Lower detector	0

	Stage control		5-axis motor drive stage	
e	Stage traverse range	Х	0~50mm	
Stage		Υ	0~50mm	
		R	360°	
iñ		Т	-5 ~ 70°	
Specime		Ζ	1.5~30mm	
О	Max. sample size		100mm dia. * 150mm dia. (Option)	

SU8030

SU8030, with its large chamber & stage for more versatile sample accommodation

SU8030 has a large specimen stage with 110mm traverse range in both of XY direction and a maximum 150mm diameter sample exchange chamber as standard (*200mm diameter option). With the combination of a stunning signal detection system and large chamber/stage, the SU8030 is a highly versatile high resolution instrument.

SU8030, with its large chamber & stage for more versatile sample accommodation.



150mm diameter specimen exchange chamber for large/multi sample observation

A REAL PROPERTY OF A REAL PROPER

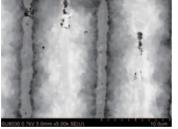
Cross section holder/stub (*Option)

Sample · Multilaver ceramic condenser

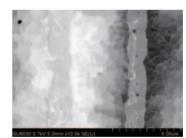


Wafer holder (*Option)



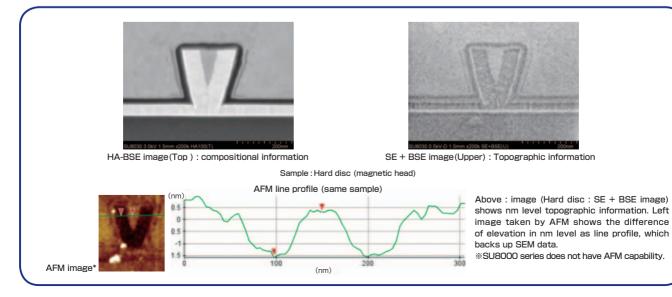


SE image (Upper)



SE image (Upper) *

* Voltage contrast image , with applied voltage by EBIC image observation unit(option)



7

Large stage with 5 axis motor drive as standard



User Interface of stage

X-Y basic control

With a trackball, or joystick(*Option)
Stage history function

The stage history function allows the operator to automatically save the stage position each time an image is captured. The saved positions can be recalled and used on subsequent sample runs. This function improves throughput and repeatability from sample to sample.

Computer eucentric tilt and rotation

The sample field of view will automatically remain in focus and centered within the field of view when the stage is tilted or rotated.

Continuous focus with Z axis movement

The focus of the image is automatically maintained as the stage Z axis is moved.

X-Y step function

The step function will move the stage in the ${\sf X}$ or ${\sf Y}$ direction by a predetermined user-defined

distance with the click of the mouse. This function is advantageous for observation and counting of repeated patterns/structures.

Graphic display of stage position

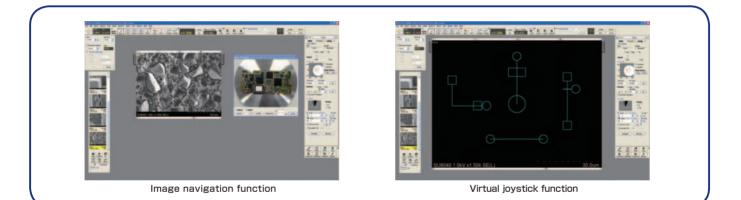
An interactive graphical interface of the stage and objective lens helps the user know the position of the sample in relation to the objective lens.

Virtual joystick

The stage can be moved with the mouse by controlling the on-screen virtual joystick.

Image navigation

The image navigation function can utilize imported color optical images, schematics or diagrams or captured low magnification SEM image to traverse the sample under investigation. A single click on the reference image will drive the sample to the chosen location.





etector	SE resolution	1.Onm(Vacc 15kV,WD=4mm) 1.3nm(landing voltage1kV,WD=1.5mm)
)et(Top detector	0
	Upper detector	0
S	Lower detector	0

	Stage control		5-axis motor drive stage	
Specime Stage	Stage traverse range	Х	0~110mm	
		Υ	0~110mm	
		R	360°	
		Т	-5 ~ 70°	
		Ζ	1.5~40mm	
o	Max. sample size		150mm dia. *200mm dia. (Option)	

SU8040

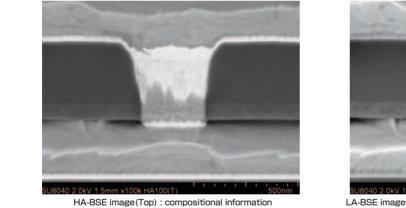
SU8040, top of the SU8000 Series range, with high performance Regulus stage^{*1} as standard

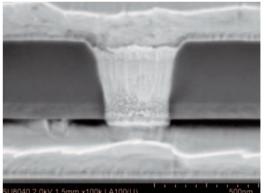
The SU8040 has the high performance Regulus stage as standard. By improving the drivetrain from the motor, the high precision stage motion has been developed for ultra-smooth motion, extending the microscope's capability for high throughput observation even at the highest magnifications.

Newly developed Regulus stage for high magnification microscopy needs



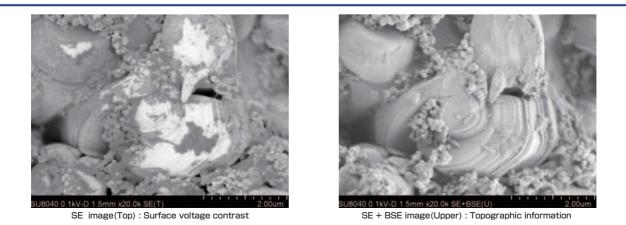
FE-SEM has grown to be an indispensable tool for the semiconductor and cutting-edge nanotechnology materials industries. These types of sample often have nm scale structures requiring ultra high magnifications. Applications such as these demand that the sample stage motion traverses smoothly and with precision during observation to assist the user's task at ultra high magnifications. To meet the needs of ultra high resolution microscopy, Hitachi has developed a new stage called Regulus. The smooth operation of the Regulus stage helps to achieve high throughput observation contributing to operator ease of use.





LA-BSE image(Upper) : Topographic + compositional information





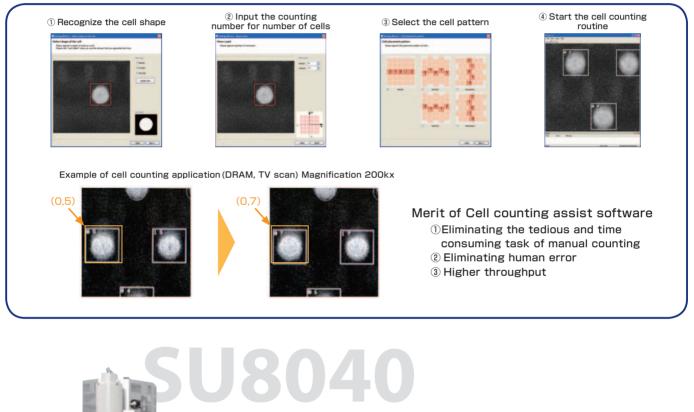
Sample : Li ion battery (Surface of negative electrode)

New cell counting software assists in locating, and following the field of interest (*Option for SU8040)

Utilizing the excellent performance of the Regulus stage, optional cell counting software is available(*Option for SU8040). Combination of the high performance Regulus stage providing smooth stage motion, and excellent SEM performance even at high speed TV scan mode will offer high reliability cell counting.

By recognizing the repeated pattern of DRAM/SRAM products, the new cell counting assist software helps to locate the target field of view.

Workflow



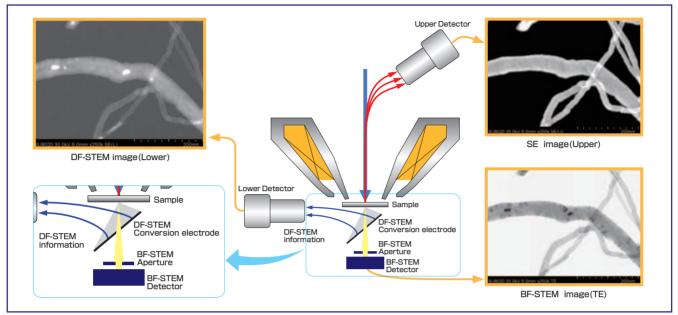


ector	SE resolution	1.0nm(Vacc 15kV,WD=4mm) 1.3nm(landing voltage1kV,WD=1.5mm)
lete	Top detector	0
	Upper detector	0
S	Lower detector	0

Ð	Stage control		5-axis motor drive stage(Regulus stage) (repeatability $\pm 0.5 \mu\text{m}$)
Specime Stage	Stage traverse range	Х	0~110mm
		Υ	0~80mm
		R	360°
		Т	-5 ~ 70°
		Ζ	1.5~40mm
Max. sample s		ize	150mm dia.

BF/DF STEM function (Option)

Observation of sample using transmitted electrons



In the SU8000 series, BF/DF-STEM detection is available for imaging thin specimens and grid-mounted samples, forming an image from the transmitted electrons.

In addition to SE imaging for surface topography observation, both Bright Field(BF)-STEM (electron absorption) and Dark Field(DF)-STEM Z-number contrast (atomic number contrast) imaging can be applied using the optional sample holders and detectors.

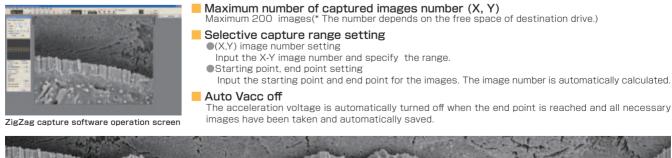
In BF-STEM observation, it is possible to obtain high contrast images even of light element materials, such as organic samples, as a result of the application of accelerating voltages up to 30kV.

Furthermore, by utilising the optional BF-STEM apertures it is also possible to obtain higher contrast imaging by controlling the detection angle.

In DF-STEM imaging the detection angle is varied by changing the hole size of the DF-STEM holder to optimize the Z (atomic number) contrast.

ZigZag capture (Option) and stitch software (Option)

The ZigZag capture software helps to obtain successive images by moving the stage automatically. By stitching the images taken by the ZigZag capture software, it is possible to obtain an ultra low magnification image or large area image at high pixel resolution.





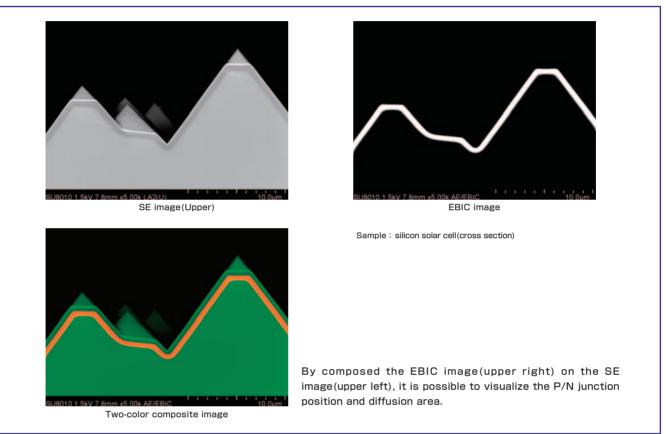
Sample : Small-intestinal villus (Rat) (each image is taken at 20kx magnification, 2 x 8 images)

EBIC image observation unit (Option, Not available for SU8040)

EBIC image(Electron Beam Induce Current Image) is widely used to identify semiconductor P/N junctions, or breakdown failure.

When the electron beam lands on the semiconductor P/N junction, an electron/hole pair is induced and electric current is passed through an external circuit. EBIC image is obtained by amplifying the electric current.

EBIC application of silicon solar cell

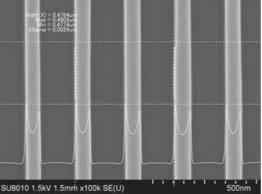


CD-Measurement (Option)



CD-measurement utilises software that can measure the specified width, or angle on the SEM image. Selectable manual measurement and auto measurement is available for various purposes. The CD-measurement algorithm is based on the Hitachi CD-SEM that has a very good reputation in the market. By using a standard sample (Optional microscale) for calibration, high accuracy CD-measurement

can be realized.



Sample : Si line and space pattern

- Width/separation/pitch auto-measurement (horizontal/vertical direction)
- Width + pitch simutaneous auto-measurement. (horizontal/vertical direction)
- Width manual measurement
- (horizontal/vertical/diagonal direction simultaneously) Angle manual measurement
- Enlargement window for a cursor selected area
 Measurement data is displayed on the image (recordable)
- + file output (text file or Microsoft Excel compatible)

SPECIFICATION

	SU8010	SU8020	SU8030	SU8040					
Secondary Electron Image Resolution			5 kV, WD=4 mm)*1 age 1kV, WD=1.5 mm)*1						
Low mag mode			nifi cation on Photo) *2						
			nifi cation on display) *3						
High mag mode			agnifi cation on Photo) *2						
		300-2,000,000 × (M	lagnifi cation on display) *3						
Electron gun		Cold cathode field emission source							
Accelerating voltag	e		(V(Standard mode)						
Landing voltage			(Deceleration mode)						
Lens system		3-stage electromagne	etic lens reduction system						
Objective lens apertu	e Objective apertu	Objective aperture(Heating type), 4 openings selectable from outside of vacuum, finely adjustable.							
Stigmator coil		Octopole electromagnetic system (X,Y)							
Scanning coil		2-stage electron	magnetic deflection						
	3-axis motor drive			5-axis motor drive					
Stage Control	5-axis motor drive *4	5-axis i	motor drive	(Regulus Stage)					
	X 0-	~ 50mm	0~110mm	0~110mm					
	Y 0-	~ 50mm	0~110mm	0~80mm					
Traverse range	R	3	360°						
Traverse range	Т		~70°						
		~ 30mm		~ 40mm					
Max. sample size		dia. (Maximum)		ia. (Maximum)					
		mm dia.*4	200 mm dia.*4						
Stage repeatabilit	/ _	-		less than \pm 0.5 μ m					
Electrical Image Shif		± 12μm	(WD=8 mm)						
Secondary electro detector	Lower/Upper	Lower/Upper Lower/Upper/Top SE/BSE Signal Mixing Function (Upper detector)							
			tor type BSED *4						
Backscattered Electron Detector			BSED ^{*4}						
			or (for BF-STEM) *4						
Transmission Electr	n	BF-STEM aperture *4							
Detector			EM holder *4						
		Energy dispersive X-ray spectrometer*4							
Other		Faraday cup*4							
Other		Cathodoluminescence detector *4							
		EBIC image observation unit ^{*4} –							
Auto evacuation		Pneumatic	valve system						
		Pneumatic valve system Electron gun chamber ~ 10 ⁻⁷ Pa							
Ultimate vacuum		3 .	namber $\sim 10^{-4}$ Pa						
Vacuum pumps Vacuum gauges		lon pump 60	I/s x 1, 20 I/s x2						
Vacuum pumps		Magnetic bearing type turbo molecular pump, 300 l/s x 1							
		Oil rotary pump 135 I/min at 50Hz (162 I/min at 60Hz) x 1							
			x1, Pirani gauge x2						
Anti-contaminatio	ł	Anti-conta	amination trap						
PC/OS		PC/AT compatib	ole, OS : Windows ^{® *5}						
External device conn	ec-		interface						
tion port			face (Ethernet) *4						
Mositor	24.	.1" type or the equivalent LCD (c	Jisplay screen image : 1,920 ×	(1,200)					
Monitor		Chamb	perscope *4						
			play (1280 × 960)						
Image display mode	s		blay (640 × 480)						
			adjustment (320 × 240)						
			display (640 × 480, × 2)						
			el display, 25/30 frames/s)*6						
		Fast scan (full screen display, 6.25/7.5 frames/s) *6							
Scanning speeds		Slow scan (full screen display, 1/4/20/40/80 s/frame)							
Scanning speeds									
	640 × 45	(640 × 480 pixel display	y, 0.5/2/10/20/40 s/frame)	X 3.840 nivele					
Scanning speeds		(640 × 480 pixel display 30pixels、1,280 × 960pixels、	y, 0.5/2/10/20/40 s/frame)	× 3,840pixels					

SU8000 Series

	SU8010	SU8020	SU8030	SU8040				
	CD-measurement *4							
	CD-measurement function for SEM Data Manager (for external PC) *4							
		Hi-Mouse (single keyboard, single mouse) *4						
Optional software			munication interface*4					
			c interface *4					
		Zigzag Ca	pture *4 & Stitch *4					
		_		cell count assist software *4				
		Wafer holde	r (2", 3", 4", 5", 6")*4					
Optional holders		_	Wafer holder (8") *4	_				
		various types of specimen	stubs and cross section holder	S *4				
		Mississies and for the second second		*4				
Other optional items			ole for magnification calibration) stick unit*4					
		JOy	Stick unit					
Temperature	15~25°C							
Humidity	less than 60% (RH) (non-condensing)							
Power (Main unit)		AC100V \pm 10%, 4kVA (Crimp contact for M5)						
Power (W-5020Td *4) Grounding Cooling water Compressed air *7		AC100V \pm 10% , 2kVA (Crimp contact for M6) *4						
Grounding		10	O Ω or less					
Cooling water		Dedicated cooling	water circulation system*4					
Compressed air *7			c1/4taper internal thread)*4					
N2 purge*7		30 to 50 kPa (Rc1/4taper internal thread) *4						
Ē		Scroll type dry pump(switching from oil rotary pump) *4						
Optional items			up unit for Ion Pump ^{*4}					
		N2 gas leak port ^{*4}						
		Auto-Transformer (for	115 \sim 240V power supply) *4					
Main unit Display unit Oil rotary pump Air compressor Weight W-5020Td*4	840(W)×970(D)	×1,680(H)、593kg	840(W)×970(D)×1,720(H 661kg), 840(W)×970(D)×1,720(H), 667kg				
Display unit	1.000(W) × 1.010(D) × 1.200(H), 205kg							
Oil rotary pump		530(W)×24	0(D) × 240(H)、28kg					
Air compressor	420(W) × 210(D) × 520(H)、16kg							
Weight		200(W)×18	0(D)×160(H)、40kg					
W-5020Td*4		400(W)×45	0(D) × 670(H)、73kg					

*1 Based on the gap (point to point) method by using Hitachi standard sample for resolution measurement

*2 at 127 mm × 95 mm (4" × 5" Picture size) *3 at 345 mm × 259 mm (1,280 × 960 pixels)

*4 option

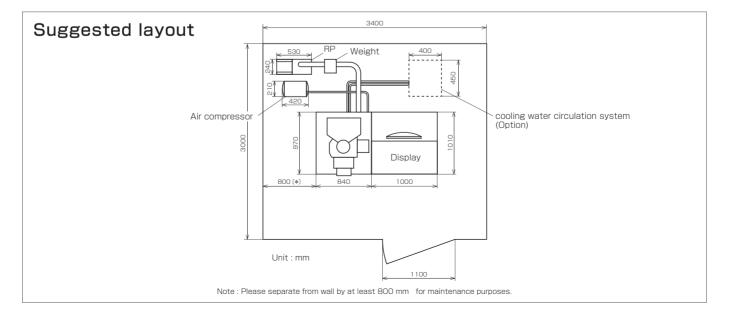
*5 Windows XP Professional is a registered trademark of U.S. Microsoft Corp. in U.S.A. and other countries.

*6 50Hz/60Hz

*7 In case of connection from the installation site facilities.

*8 Weight does not include options

% For disposal of this product, please contact your nearest sales representative.



Notice: For correct operation, follow the instruction manual when using the instrument.

Specifications in this catalog are subject to change with or without notice, as Hitachi High-Technologies Corporation continues to develop the latest technologies and products for our customers.

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